











- As VDS is increased towards a value VP (pinch off voltage), the depletion region is widened and channel width is reduced increasing resistance to ID and the two depletion regions will appear as touching each other

-These two effects result in ID being kept almost constant















## Pinch off voltage:

- ✓ The voltage that cusses the depletion region to touch and close the channel is called pinch off voltage
- $\checkmark$  For the n-channel JFET to be in the pinch off region:

$$V_P < V_{GS} \le 0$$

 $|V_{DS}| > |V_P| - |V_{GS}|$ 

 $\checkmark$  For the p-channel JFET to be in the pinch off region:

$$|V_{DS}| > |V_P| - |V_{GS}|$$

 $V_P > V_{GS} \geq 0$ 

## **Common JFET Biasing Circuits**

- Fixed-Bias
- Self-Bias
- Voltage-Divider Bias





























































## Operation , characteristic and parameters of EMOSFET

- On the application of  $V_{DS}$  and keeping  $V_{GS}$ =0 practically zero current flows .
- If we increase  $V_{\rm GS}$  in the positive direction the concentration of electrons near the Si $O_2$  surface increases ,
- At particular value of  $V_{GS}$  there is a measurable current flow between drain and source ;  $I_{DS}$  .
- This value of  $V_{GS}$  is called threshold voltage denoted by  $V_T$  or V<sub>GS(TH)</sub>
- A positive  $V_{GS}$  above  $V_T$  induce a channel and hence the drain current  $(I_{DS})$  by creating a thin layer of negative charges (electrons) in the substrait adjacent to the Si $O_2$  large.

















